

(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Beaman et al.

Application No.: 10/646,673

Confirmation No.: 1020

Filed: August 21, 2003

Art Unit: 1762

For: METHODS AND APPARATUS FOR  
PROCESSING MICROFEATURE  
WORKPIECES; METHODS FOR  
CONDITIONING ALD REACTION  
CHAMBERS

Examiner: David Turocy

**INFORMATION DISCLOSURE STATEMENT (IDS)**

MS RCE  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO/SB/08. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement, pursuant to 37 CFR 1.114(c), accompanies the Request for Continued Examination (37 CFR 1.114) submitted herewith.

Applicants have not submitted a copy of each cited U.S. patent and U.S. patent application as required by 37 CFR 1.98(a)(2)(i), amended October 2004, as the U.S. Patent and Trademark Office has waived this requirement for all U.S. patent applications.

Applicants submit herewith a copy of the cited foreign and non-patent literature in accordance with 37 CFR 1.98(a)(2).

In accordance with 37 CFR 1.97(g), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined in 37 CFR 1.56(a) exists. In accordance with 37 CFR 1.97(h), the filing of this Information Disclosure statement shall not be construed to be an admission that any patent, publication or other information referred to therein is "prior art" for this invention unless specifically designated as such.

It is submitted that the Information Disclosure Statement is in compliance with 37 CFR 1.98 and the Examiner is respectfully requested to consider the listed references.

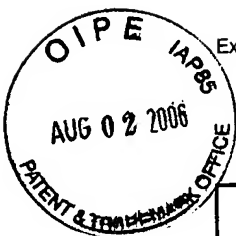
The Director is hereby authorized to charge any deficiency in the fees filed, asserted to be filed or which should have been filed herewith (or with any paper hereafter filed in this application by this firm) to our Deposit Account No. 50-0665, under Order No. 108298715US.

Dated: August 2, 2006

Respectfully submitted,

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Express Mail No. EV881810970US

Attorney Docket No. 108298715US  
Disclosure No. 03-0117.00/USPTO/SB/08a/b (07-05)  
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<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (Use as many sheets as necessary)				<b>Complete If Known</b>	
				Application Number	10/646,673-Conf. #1020
				Filing Date	August 21, 2003
				First Named Inventor	Kevin L. Beaman
				Art Unit	1762
				Examiner Name	David Turocy
Sheet	1	of	2	Attorney Docket Number	108298715US

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)			
		US-4,923,715	05-08-1990	Matsuda et al.	
		US-3,620,934	11-16-1971	Endle	
		US-5,020,476	06-04-1991	Bay et al.	
		US-5,366,557	11-22-1994	Yu	
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		US-6,251,190	06-26-2001	Mak et al.	
		US-6,689,220	02-10-2004	Nguyen	
		US-6,887,521	05-03-2005	Basceri	
		US-11/115,728	Filed 04-26-2005	Qin	

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
		Country Code <sup>3</sup> -Number <sup>4</sup> -Kind Code <sup>5</sup> (if known)	MM-DD-YYYY			
		JP-63-111177-A	05-16-1988	Hitachi Ltd.		
		JP-6-342785-A	12-13-1994	Fujitsu Ltd.		

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. \* CITE NO.: Those application(s) which are marked with an single asterisk (\*) next to the Cite No. are not supplied (under 37 CFR 1.98(a)(2)(iii)) because that application was filed after June 30, 2003 or is available in the IFW. <sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> See Kinds Codes of USPTO Patent Documents at [www.uspto.gov](http://www.uspto.gov) or MPEP 901.04. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
		Aera Corporation, "Fundamentals of Mass Flow Control," 1 page, retrieved from the Internet on March 6, 2003, < <a href="http://www.aeramfc.com/funda.shtml">http://www.aeramfc.com/funda.shtml</a> >.	
		Electronic Times, "Atomic Layer Deposition Chamber Works at Low Temperatures," 2 pages, 12/11/2001, 2001 CMP Europe Ltd., < <a href="http://www.electronicstimes.com/story/OEG20010719S0042">http://www.electronicstimes.com/story/OEG20010719S0042</a> >	
		EMCO Flow Systems, "Mach One Mass Flow Controllers", 1 page, retrieved from the Internet on November 7, 2003, < <a href="http://emcoflow.com/mach-one.htm">http://emcoflow.com/mach-one.htm</a> >.	

Examiner Signature		Date Considered	
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PTO/SB/08a/b (07-05)

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<b>Substitute for form 1449A/B/PTO</b>  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  <i>(Use as many sheets as necessary)</i>				<b>Complete if Known</b>	
				Application Number	10/646,673-Conf. #1020
				Filing Date	August 21, 2003
				First Named Inventor	Kevin L. Beaman
				Art Unit	1762
				Examiner Name	David Turocy
Sheet	2	of	2	Attorney Docket Number	108298715US

		EMCO Flow Systems, "Mach One Mass Flow Controller Product Brochure" 6 pages, retrieved from the Internet on November 7, 2003, < <a href="http://www.emcoflow.com/literature/brochures_product_sheets/mach_one/mach_one_brochure_2_01.pdf">http://www.emcoflow.com/literature/brochures_product_sheets/mach_one/mach_one_brochure_2_01.pdf</a> >.	
		SemiZone, "EMCO Flow Systems Granted Patent for the Mach One Mass Flow Controller for the Semiconductor Industry (June 28, 2001), 2 pages, retrieved from the Internet on November 7, 2003, < <a href="http://www.semizone.com/news/item?news_item_id+100223">http://www.semizone.com/news/item?news_item_id+100223</a> >.	
		TAKAHASHI, K et al., "Process Integration of 3D Chip Stack with Vertical Interconnection," pp. 601-609, 2004 Electronic Components and Technology Conference, IEEE, June 2004.	

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup>Applicant's unique citation designation number (optional). <sup>2</sup>Applicant is to place a check mark here if English language Translation is attached.

Examiner Signature		Date Considered	
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